Number	Hits		DB	Time stamp
2	767	(tft or thin adj film adj transistor) and etching near gate	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/05/26
3	271	polysilicon and ((tft or thin adj film adj transistor) and etching near gate)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/05/26 10:34
4	53	thinning and ((tft or thin adj film adj transistor) and etching near gate)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/05/26 10:39
5 .	12	"5614728"   "5789778"   "5834352"   "5874329"   "6017781"   "6066535"	IBM_TDB USPAT	2004/05/26 10:36
	4159	- 1 0220044 ).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/05/26 10:40
7	767	((tft or thin adj film adj transistor) and etching near gate) and ((thining or etching) near gate)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/05/26 10:40
8	243	cmos and (((tft or thin adj film adj transistor) and etching near gate) and ((thining or etching) near gate))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/05/26 10:40
9	162	(ldd or lightly adj doped adj drain) and (cmos and (((tft or thin adj film adj transistor) and etching near gate) and ((thining or etching) near gate)))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/05/26 10:56
10	1	sacrificial adj gate and (cmos and ((tft or thin adj film adj transistor) and etching near gate) and ((thining or etching) near gate))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; -DERWENT;	2004/05/26 10:56
11	16914	(ldd or lightly adj doped adj drain)	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/05/26 10:56
12 <sup>°</sup>	243	sacrificial adj gate	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/05/26 10:56
13	72	((ldd or lightly adj doped adj drain) ) and (sacrificial adj gate)	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/05/26
			DERWENT; IBM TDB	